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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
09/775,059	02/01/2001	Fan Piao	39153/306 (F0793)	8057	
7	590 04/01/2004		EXAMINER		
Joseph N. Ziebert			CHACKO DAVIS, DABORAH		
FOLEY & LARDNER Firstar Center			ART UNIT	PAPER NUMBER	
777 East Wisconsin Avenue			1756		
Milwaukee, WI 53202-5367			DATE MAILED: 04/01/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)	· · · · · · · · · · · · · · · · · · ·	~			
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Office Action Summary		09/775,059	PIAO, FAN					
		Examiner	Art Unit					
	The MAILING DATE of this communication app	Daborah Chacko-Davis	1756	Idroce				
Period fo		lears on the cover sheet with the c	orrespondence ad	iaress				
THE - Exte after - If the - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. It is period for reply specified above is less than thirty (30) days, a reply of period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ting within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	nely filed rs will be considered timel the mailing date of this of D (35 U.S.C. § 133).					
Status								
1)⊠	Responsive to communication(s) filed on 29 De	<u>ecember 2003</u> .						
2a)⊠	This action is FINAL . 2b) ☐ This	action is non-final.						
3)[Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Dispositi	ion of Claims							
5)□ 6)⊠ 7)□ 8)□ Applicati 9)□	Claim(s) 7-14 and 21-32 is/are pending in the at 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed. Claim(s) 7-14, 21-32 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or for Papers The specification is objected to by the Examiner is/are is/are as is/are a	r.	·					
10)	The drawing(s) filed on is/are: a) acce	•						
	Applicant may not request that any objection to the o			ED 4 404(4)				
11)	Replacement drawing sheet(s) including the correction. The oath or declaration is objected to by the Ex			, ,				
Priority ι	ınder 35 U.S.C. § 119							
a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau See the attached detailed Office action for a list of	s have been received. s have been received in Applicati ity documents have been receive (PCT Rule 17.2(a)).	on No ed in this National	Stage				
Attachmen	t(s)							
2) Notic 3) Inform	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	ate	O-152)				

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DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 7-14, and 21-31, are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 6,097,361 (Rohner) in view of WO 98/06560 (Narang et al).

Rohner, in col 1, lines 8-12, in col 3, lines 43-63, and in col 4, lines 1-67, and in col 5, lines 1-7, in col 6, lines 60-63, in col 7, lines 18-34, and in col 12, lines 45-47, discloses a method of manufacturing an integrated circuit comprising providing a pattern of radiation via an LCD assembly and a (reduction lens system (reference 26) (means for focusing the light on the wafer) and performing a semiconductor fabrication process with a pattern of radiation, and providing a second pattern of radiation via the LCD panel to perform a second semiconductor fabrication with the second pattern of radiation, and discloses that the LCD assembly is coupled to a computer system via display driver, control unit, and memory unit. Rohner, in col 7, lines 18-34, discloses that the LCD panel receives the display signals and displays the desired pattern in response to the display signals, wherein the control unit is adapted for coupling the external computer system inorder to receive the display data from the computer system

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and is configured to store the display data within the memory unit. Rohner, in col 7, lines 17-34, discloses that the memory unit stores data necessary to display a desired pattern upon the LCD panel (means for providing a pattern of light), wherein the control unit is adapted to a computer system in order to display data from the computer system (means for controlling the means for providing, and selecting the pattern) and configured to store the data (database) within the memory unit in order to forward the display data (from a workstation executing a software program) via the display driver that produces multiple display signals to the LCD panel (claims 7-8, 14, 21, 23, and 25-28). Rohner, in col 4, lines 9-40, in col 6, lines 25-41, discloses that a step-and repeat process is performed to produce the pattern on the light sensitive layer on the substrate (claim 9). Rohner, in col 1, lines 1-20, discloses that the integrated circuits are produced by patterning layers in succession to form features (metal lines) (interconnects) that comprise elements of an integrated circuit (application specific IC) (claims 10, 13, 22, and 24). Rohner, in col 10, lines 38-67, and in col 11, lines 1-10, discloses that the pattern structure is that of a MOS transistor (claim 11). Rohner, in col 3, lines 61-67, and in col 4, lines 1-8, and lines 21-25, discloses that the pattern is stored electronically (memory unit configures the LCD display data) (claim 12). Rohner, in col 10, lines 38-62, and in figure 6a, discloses that the image data includes application specific IC information, such as two-dimensional matrix transparent pixel electrodes, and corresponding electrical switching elements as in MOS transistors (claims 29, and 31). Rohner, in col 7, lines 22-23, and lines 49-65, discloses that the image data is stored in the memory unit, and that the

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memory unit comprises DRAM devices, and alternatively programmable readonly memory devices (storage media) (claim 30).

The difference between the claims and Rohner is that Rohner does not disclose that a) the control signal is generated by the software to select a plurality of components, wherein each component is associated with individual image data, the individual image data being stored in a database; and b) the computer generates the control signal from the individual image data associated with the corresponding components.

Narang, on page 5, lines 20-30, and on page 6, lines 1-13, discloses that the photoexposure process includes a CAD/CAM system that comprises a means for producing a pattern of radiation (control signal) (a 3-D computer model representation of the object), a means for slicing the representation of the object (plurality of components) into successive layers, means for producing cross section data of the layers of the object (individual image data), and means for providing the cross section data to the computer controlled selective photoexposure means (LCD projector).

Therefore, it would be obvious to a skilled artisan to modify Rohner by employing the method of producing a control signal that corresponds to the individual image data (slice data, cross section data) as taught by Narang because Narang, on page 5, lines 15-30, discloses that employing such a method enables the automated layer-by-layer fabrication of a three-dimensional object from a computer model of the object.

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3. Claim 32 is rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 6,097,361 (Rohner) in view of WO 98/06560 (Narang et al) as applied to claims 7-14, and 21-31, above, and further in view of EP 0315589 (Ciba-Geigy).

Rohner is discussed in paragraph no. 2.

The difference between the claim and Rohner is that Rohner does not disclose that the control signal is a video signal.

Ciba-Geigy, in col 4, lines 47-65, discloses that image signal (control signal) is retrieved form a video output.

Therefore, it would be obvious to a skilled artisan to modify Rohner in view of Narang by using the video output devices as the control signal as taught by Ciba-Geigy because Rohner does not limit the display signal to a particular type, and Ciba-Geigy, in col 5, lines 64-65, and in col 6, lines 1-8, discloses that using a video signal enables the operator to view a real-time image of the altered slide image.

Response to Arguments

- 4. Applicant's arguments with respect to claims 7-14, 21-32, have been considered but are moot in view of the new ground(s) of rejection.
- A) Applicant argues that Rohner does not teach generating a control signal from individual images associated with chosen components to configure a mask.

Applicant's argument (directed to the currently filed amendment) is addressed in the new grounds of rejection. See paragraph no. 2.

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Conclusion

5. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from

either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

dcd MM

March 24, 2004.

MARK F. HUFF SUPERVISORY PATENT EXAMINER

TECHNOLOGY CENTER 1700